

## METHOD FOR MANUFACTURING A SEMICONDUCTOR DEVICE

### **ABSTRACT OF THE DISCLOSURE**

A method of forming patterns in a semiconductor device comprises:  
5 forming a conductive film on a substrate; forming an anti-reflective layer on the  
conductive film; cleaning oxide residues on the anti-reflective layer using a first  
cleaning solution; cleaning the oxide residues on the anti-reflective layer using a  
second cleaning solution; forming a photoresist pattern on the anti-reflective  
layer; and patterning the conductive film using the photoresist pattern.